Third Semester B.E. Degree Examination, June/July 2023 **Electronic Devices**

Time: 3 hrs.

Max. Marks: 100

Note: Answer any FIVE full questions, choosing ONE full question from each module.

Module-1

Explain direct and indirect semiconductors with neat sketches and giving examples. 1

(06 Marks)

- Define:
 - Intrinsic semiconductor i)
 - Amphoteric Impurity ii)
 - Electron mobility iii)

Hall Effect. iv)

(08 Marks)

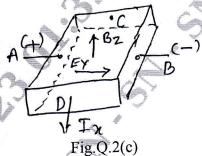
A silicon is doped with 10¹⁷ Arsenic atoms/cm³. What is the equilibrium hole concentration po at 300°K? Sketch the resulting band diagram showing where is E_F relative to Ei. Assume (06 Marks) $ni^2 = 2.25 \times 10^{20}$.

Explain effects of temperature and doping on mobility. 2

(08 Marks)

Explain the formation of extrinsic semi conductor with covalent bonding model diagram. b.

Consider a semiconductor bar with W = 0.1mm, t = 10mm and L = 5mm. For $B_2 = 10$ kG in the direction shown in Fig.Q.2(c) and a current of 1mA, $V_{AB} = -2mV$, and $V_{CD} = 100 \text{mV}$. Find the type of semiconductor carriers and mobility of the majority carrier. Given (06 Marks) $1KG = 10^{-5} \text{wb/cm}^2$



Differentiate Zener and Avalanche breakdown. 3

(06 Marks)

Explain the requirement for the design of rectifier diode. b.

(06 Marks)

Explain the working of solar cell and mention the applications of LED.

(08 Marks)

OR

Mention the applications of photo diode.

(06 Marks)

Explain the current and voltage in an illuminated junction by deriving the expression for

A solar cell has a short circuit current of 100mA, and an open circuited voltage of 0.8V under full solar illumination. What is the power delivered by the cell which is having a fill (06 Marks) factor of 0.72

2. Any revealing of identification, appeal to evaluator and /or equations written eg, 42+8 = 50, will be treated as malpractice. Important Note: 1. On completing your answers, compulsorily draw diagonal cross lines on the remaining blank pages.

Module-3

			<u>Modute-3</u>	
	5	a.	Derive the relationship between α and β of a transistor.	(06 Marks)
		b.	Explain switching action of transistor.	(08 Marks)
		c.	A symmetrical p ⁺ np ⁻ bipolar transistor has the following properties:	
		•	Emitter Base	
			$A = 10^{-4} \text{ cm}^2$ $N_a = 10^{17}$ $N_d = 10^{15} \text{ cm}^{-3}$	
			$W_b = 1 \mu m$ $t_n = 0.1 \mu s$ $t_p = 10 \mu s$	
			$\mu_p = 200$ $\mu_n = 1300 \text{cm}^2 \text{ v.s}$	
			$\mu_{\rm n} = 700$ $\mu_{\rm p} = 450 {\rm cm}^2 {\rm v.s}$	
			Assume ni = 1.5×10^{10} /cm ³ . Find base current.	(06 Marks)
			OR	
	6	0	Explain the working of pnp transistor with necessary figures.	(08 Marks)
	O	a.		(06 Marks)
		b.	Explain BJT fabrication process.	
		c.	Explain drift in the base region.	(06 Marks)
			Module-4	
	7	a.	Explain n-channel PNJFET operation with its characteristics.	(10 Marks)
		b.	Mention the difference between JFET and MOSFET.	(04 Marks)
,		c.	Explain the MOS structure with aid of parallel plate capacitor.	(06 Marks)
			OR	
	8		Explain the operation of p-channel depletion and enhancement type MOSFET	with neat
	0	a.		(10 Marks)
			sketches.	
		b.	Mention the applications of MOSFET.	(04 Marks)
		C.	Draw and explain small signal equivalent circuit of a n-channel PNJFET.	(06 Marks)
			Module-5	
	9	a.	Mention the advantages of IC's over discrete components.	(06 Marks)
		b.	Explain photolithography process.	(06 Marks)
		c.	Explain the working of CMOS inverter with neat diagram.	(08 Marks)
			OR OR	
	10	a.	Explain thermal oxidation and diffusion process of the semiconductor fabrication.	
	10	a.	Explain thermal oxidation and diffusion process of the semiconductor morreation.	(08 Marks)
		b.	Explain integration of other circuit elements.	(08 Marks)
			Define: i) Etching ii) Metallization.	(04 Marks)
		C.,	Define. I) Etching II) Metanization.	(04 Marks)
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